Jong Sik Oh

List of Publications by Year
in descending order

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18 papers	222 citations	1163117 8 h-index	996975 15 g-index
18 all docs	18 docs citations	18 times ranked	429 citing authors

#	Article	IF	Citations
1	Invisible Silver Nanomesh Skin Electrode via Mechanical Press Welding. Nanomaterials, 2020, 10, 633.	4.1	14
2	Efficient metallic nanowire welding using the Eddy current method. Nanotechnology, 2019, 30, 065708.	2.6	7
3	Fabrication of high-performance graphene nanoplatelet-based transparent electrodes <i>via</i> self-interlayer-exfoliation control. Nanoscale, 2018, 10, 2351-2362.	5.6	7
4	Fabrication of Stretchable Transparent Electrodes. Applied Science and Convergence Technology, 2017, 26, 149-156.	0.9	3
5	Purification of Graphene Flakes by Using Radio-Frequency Thermal Ar Plasma. Science of Advanced Materials, 2016, 8, 891-897.	0.7	0
6	Nano-Welding of Ag Nanowires Using Rapid Thermal Annealing for Transparent Conductive Films. Journal of Nanoscience and Nanotechnology, 2015, 15, 8647-8651.	0.9	13
7	Graphene Doping Methods and Device Applications. Journal of Nanoscience and Nanotechnology, 2014, 14, 1120-1133.	0.9	50
8	Effect of Plasmaâ€“Nitric Acid Treatment on the Electrical Conductivity of Flexible Transparent Conductive Films. Japanese Journal of Applied Physics, 2013, 52, 075102.	1.5	8
9	Plasma Treatment of Thin Film Coated with Graphene Flakes for the Reduction of Sheet Resistance. Journal of Nanoscience and Nanotechnology, 2013, 13, 8090-8094.	0.9	2
10	Electron-injecting properties of Rb2CO3-doped Alq3 thin films in organic light-emitting diodes. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2013, 31, 031101.	2.1	6
11	Characteristics of SiO thin films deposited by atmospheric pressure chemical vapor deposition using a double-discharge system. Materials Research Bulletin, 2012, 47, 3011-3014.	5.2	5
12	Ion Bombardment during the Deposition of SiO[sub X] by AC-Biasing in a Remote-Type Atmospheric Pressure Plasma System. Journal of the Electrochemical Society, 2011, 158, G58.	2.9	6
13	Characteristics of SiOx thin films deposited by atmospheric pressure chemical vapor deposition as a function of HMDS/O2 flow rate. Thin Solid Films, 2010, 518, 6403-6407.	1.8	19
14	Polyimide Surface Treatment by Atmospheric Pressure Plasma for Metal Adhesion. Journal of the Electrochemical Society, 2010, 157, D614.	2.9	30
15	High-speed etching of SiO2using a remote-type pin-to-plate dielectric barrier discharge at atmospheric pressure. Journal Physics D: Applied Physics, 2010, 43, 425207.	2.8	3
16	Plasma texturing of multicrystalline silicon for solar cell using remote-type pin-to-plate dielectric barrier discharge. Journal Physics D: Applied Physics, 2009, 42, 215201.	2.8	18
17	Characteristics of SiO[sub x] Thin Film Deposited by Atmospheric Pressure Plasma-Enhanced Chemical Vapor Deposition Using PDMSâˆ•O[sub 2]âˆ•He. Journal of the Electrochemical Society, 2009, 156, D248.	2.9	14
18	X-ray photoelectron spectroscopic study of Ge2Sb2Te5 etched by fluorocarbon inductively coupled plasmas. Applied Physics Letters, 2008, 93, .	3.3	17